

Abstract

The invention relates to a recycling method and to a recycling device for recycling waste water containing slurry from a semiconductor treatment process, in particular from a chemico-mechanical polishing process. Said method consists of the following steps: a filtration step in which waste water containing the fresh slurry is continuously introduced into a circulation tank (10), during which time the mixed waste water is continuously extracted from the circulation tank (10), the extracted waste water is guided through an ultra filter device (20) and is concentrated by removing the fluid to form concentrated waste water and the concentrated waste water is introduced into the circulation tank (10) and mixed with the contents of the circulation tank (10) in order to obtain the mixed waste water; and a concentration step which follows the filtration step in which the addition of fresh waste water to the circulation tank (10) is prevented or essentially stopped when the mixed waste water is continuously extracted from the circulation tank (10), said extracted mixed water waster being introduced through the ultra filter device (20) and is concentrated by removing the fluid to form concentrated waste water and the concentrated waste water is introduced into the circulation tank (10).